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P A T E N T

Attorney Docket No.
033082M172

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:)	CONFIRMATION NO.: 1732
)	
Takanori MIMURA, et al.)	
)	
U.S. Serial No.: 10/647,433)	Group Art Unit: 1765
)	
Filed: August 26, 2003)	Examiner: Binh X. Tran
For: SILICON ETCHING METHOD		

RESPONSE TO ELECTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir :

A response to the Office Action mailed August 29, 2005 is due by September 29, 2005.

The Action required election between the following:

Species A, with a SiO₂ film mask, and a RF power flux density at 6.8 to 12.5 W/cm²; and

Species B, with a resist film, and a RF power flux density at 2.55 to 5.67 W/cm².

Applicants hereby elect Species A for examination in this application. Applicants advise that the elected species corresponds to all of claims 1-15 and 17-19. Applicants also advise that no change in the inventorship of the application would be required by cancellation of non-elected claim 16.

Applicants reserve the right to file divisional application(s) for any non-elected claims in due course.

It is submitted that this application now is in condition for examination on the merits and early action in that regard is solicited.

Respectfully submitted,

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